

ABSTRACT OF THE DISCLOSURE

A method of fabricating a photomask is disclosed. The method facilitates accurate measurement of the photomask critical dimension, without requiring the removal of the pellicle. A first pattern is transferred on a substrate in a first area, and at least one test pattern is transferred on the substrate outside of the first area. A pellicle is attached to the substrate, and the pellicle covers the first area, but does not cover the at least one test pattern.

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